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Application Number		10598943
Filing Date		2006-09-15
First Named Inventor	Peng-Fei Fu	
Art Unit	<del>4762</del> 1794	
Examiner Name	<del>Unknown</del> D. S. Nakarani	
Attorney Docket Number	071038.00102	

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/DSN/	1	WO99/26112	WO		1999-05-27	DHAL et al.		<input type="checkbox"/>
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Examiner Name	<del>Unknown</del> D. S. Nakarani
Attorney Docket Number	071038.00102

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/DSN/	2	CRIVELLO ET AL., "The UV Cure of Epoxy-Silicone Monomers, Polymeric Materials Science and Engineering, 1989, pages. 217-227, XP009035836.	<input type="checkbox"/>
/DSN/	3	LABIANCA ET AL., "High Aspect Ratio Resist For Thick Film Applications", Advances In Resist Technology and Processing XII, Spie, 1995, Vol. 2438, pages 846-852, XP002437324.	<input type="checkbox"/>
/DSN/	4	MATSUI ET AL., "Room-temperature nanoimprint and nanotransfer printing using hydrogen silsequioxane", Journal of Vacuum Science & Technology B: Microelectronics Processing and Phenomena, American Vacuum Society, March 2003, Vol. 21, No. 2, pages 688-692, XP012009826.	<input type="checkbox"/>
/DSN/	5	PFEIFFER ET AL., "Reactive Polymers - a Route to Nanoimprint Lithography at Low Temperatures", Proceedings of Spie, Spie, 2003, Vol 5037, pages 203-210, XP-002297929.	<input type="checkbox"/>
/DSN/	6	PFEIFFER ET AL., "Multistep profiles by mix and match of nanoprint and UV lithography", Microelectronic Engineering, 2001, Vol. 57-58, pages 381-387, XP004302289.	<input type="checkbox"/>
/DSN/	7	SUN XIAOYUN ET AL., "Multilayer resist methods for nanoimprint lithography on nonflat surfaces", Journal of Vacuum Science & Technology B: Microelectronics Processing and Phenomena, American Vacuum Society, 1998, Vol. 16, No. 6, pages 3922-3925, XP012007311.	<input type="checkbox"/>
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Examiner Signature	/D. S. Nakarani/	Date Considered	06/18/2009
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